



SCE-150 Spin Coater

- Rotational speed up to 9.000 rpm
- Rotational speed ramp function
- Programmable ramp duration: 3 s .. 600 s
- Programmable dwell time: 3 s .. 600 s
- Alphanumeric four-line display (20 characters/line)
- Settings stored in non-volatile memory
- Display of remaining processing time
- Total process times: 6 s .. 20 minutes
- Active vacuum suction of the sample
- Film thickness range 10 nm to 10 μ m
- Easy-to-use and maintenance free design
- Rotational platforms for substrates up to 90 mm diameter

SCE-150

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Our SCE-150 spin coater with ramp function help you prepare thin films easily within a few minutes. Films are produced on a substrate that is fixed to an exchangeable rotational platform by a pump-generated underpressure.

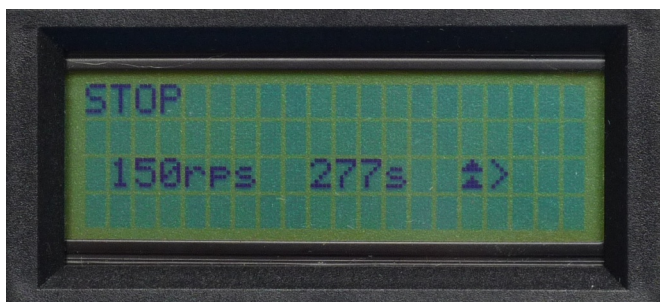
Both circular and rectangular substrates up to 90 mm diameter can be placed on the rotational platform (various sizes available, see the accessories list).

The resulting film thickness merely depends on the solid/solvent concentration, rotational speed, and time.

The ergonomic design makes the SCE-150 spin coater an efficient tool for the preparation of thin films of organic and inorganic substances for microscopic or spectroscopic investigations.

Spin coating using the SCE-150 spin coater neither requires specific skills nor prior experience and is maintenance free.

Operating and setting up the SCE-150 spin coater is easily performed using a single-know control.



During operation, a built-in digital LC display with 20 characters per line informs about the rotation speed and the remaining ramp or dwell times for testing under reproducible conditions. It also substantially facilitates the set-up of the spin coater. For the sake of reproducibility, the set-up is stored permanently in the SCE-150 non-volatile memory.

The ramp and dwell times may be varied over a wide range, i.e., between 3 s and 600 s, total process times between 6 s and 10 minutes.

Using the SCE-150 spin coater, thin and ultra thin layers of extraordinary homogeneity are easily achieved.

As a high quality product, these spin coater come with 2 years guarantee.

Accessories for the SCE-150 spin coater

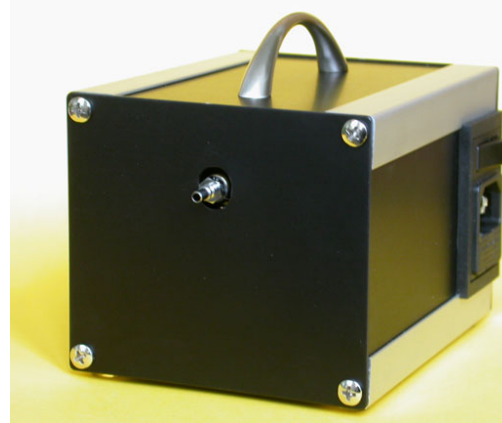
- Vacuum pump MVP with hose and quick coupling (highly recommended)
- VT-25p: rotational platform (plane chuck; Ø 25 mm, for small and irregularly shaped substrates)
- VT-25pr6: VT-25p with inserted O-ring 6x1
- VT-25pr20: VT-25p with inserted O-ring 20x1
- VT-25pr: VT-25p with inserted O-rings 6x1 and 20x1
- VT-30: rotational platform (Ø 30 mm)
- VT-50: rotational platform (Ø 50 mm)
- VT-70: rotational platform (Ø 70 mm)
- VT-90: rotational platform (Ø 90 mm)

All rotational platforms are made of aluminium.

Regular platforms are equipped with small channels on their surface to ensure uniform pressure on the substrate.

Plane platforms lack these channels; evacuation is performed exclusively through the center hole. This arrangement is better suited for small or irregularly shaped substrates that would leave major parts of the channel structure uncovered.

The SCE-150 spin coater comes with a switching power supply and a VT-30 rotational platform.



Small Vacuum Pump MVP

- Underpressure of -33,3 kPa
- Flow of 7 litres/min
- Max. 40 dB(A) noise
- Exact appearance may vary.